
Abstract

A plasma processing apparatus (5) comprises an outer shell (51) which is provided with a reaction chamber (52) in the interior, a bottom electrode which is arranged in the reaction chamber (52) and a
5 cantilever support device (53) which goes through the outer shell (51) and supports the bottom electrode. The cantilever support device (53) is pivotally mounted on the side wall of the outer shell (51) and can rotate in the outer shell (51). The plasma processing apparatus (5) further
10 comprises a locating device so as to selectively fix the relative position of the cantilever support device (53) and the outer shell (51).

Figure accompanying with the abstract: Fig.5



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